

## SiOC films by PEALD with excellent conformality and wet etch resistance

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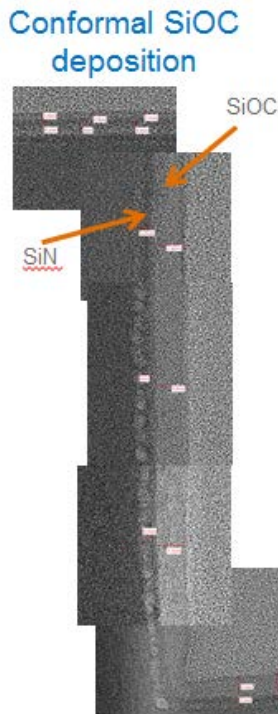


Figure 1. HR-TEM analysis of SiOC films on AR10:1 structure

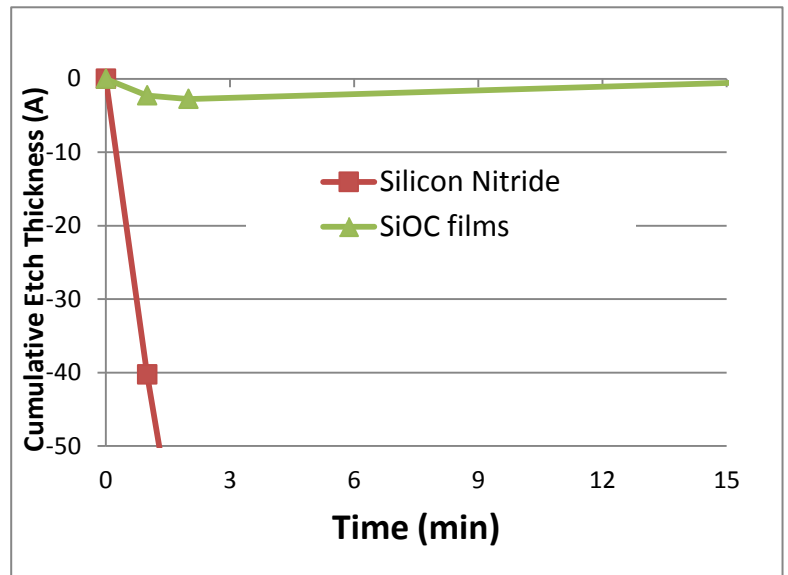


Figure 2. Cumulative etch thickness vs wet etch time in dHF 1:100 of SiN and PEALD-SiOC films